

## Supporting Information

### High-performance Optoelectronic Memory Based on Bilayer MoS<sub>2</sub> grown by Au catalyst

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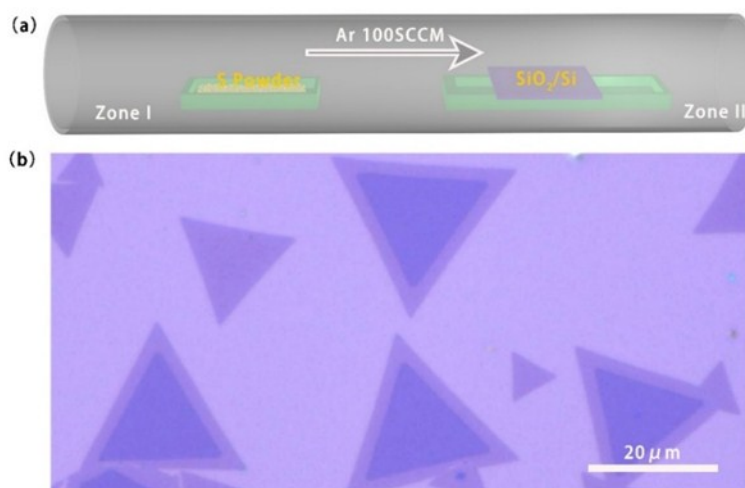
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**Fig. S1** Monolayer and bilayer MoS<sub>2</sub> directly synthesis on SiO<sub>2</sub>/Si substrate without functionated pretreatment. (a) Schematic of the CVD setup for synthesis the monolayer and bilayer MoS<sub>2</sub>. (b) Optical microscope image of MoS<sub>2</sub> grown on SiO<sub>2</sub>/Si substrate by CVD.

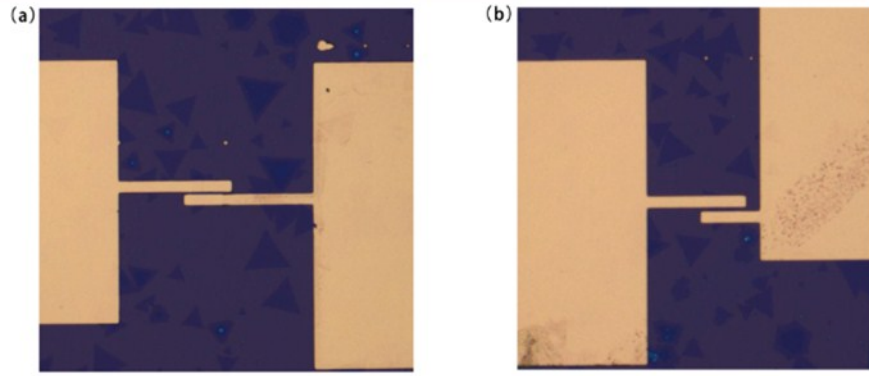


Fig. S2 Optical images of optoelectronic memory based on the monolayer and bilayer MoS2

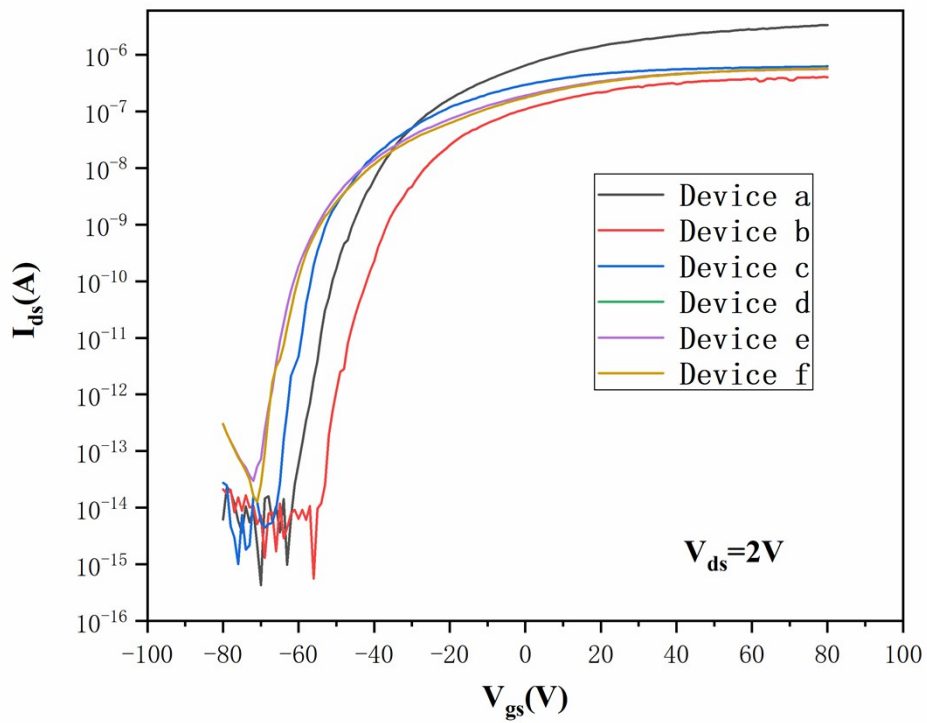


Fig. S3 Transfer characteristics of the Different devices at  $V_{ds} = 2$  V.

Table S1 Ra and Rq of the monolayer and bilayer MoS2.

Roughness	Ra (nm)	Rq (nm)
Monolayer MoS2	0.131	0.173
Bilayer MoS2	0.0849	0.107

**Table S2 Comparison between existing MoS<sub>2</sub> memory and our bilayer MoS<sub>2</sub> memory..**

<b>MoS<sub>2</sub> memory structure</b>	<b>on/off ratio</b>	<b>Retention time</b>	<b>Cyclic</b>	<b>Reference</b>
Planar Au/Ti/MoS <sub>2</sub> /Ti/Au	8×10 <sup>4</sup>	2.2×10 <sup>4</sup> s	>10	Our work
Planar Au/Cr/MoS <sub>2</sub> /Cr/Au/ substrate Si/Au/Al <sub>2</sub> O <sub>3</sub> /AuNPs/cPVP	~10 <sup>5</sup>	10 <sup>3</sup> s	>200	<i>ACS Appl. Mater. Interfaces</i> 2017, 9, 31, 26357-26362
Planar Au/MoS <sub>2</sub> /Au	4700	10 <sup>4</sup> s	————	<i>Nature communications</i> , 2017, 8, 14734